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(54) Title (EN): GAS LEAK SENSING SYSTEM AND GAS LEAK SENSING METHOD

(54) Title (FR): SYSTÈME DE DÉTECTION DE FUITE DE GAZ ET PROCÉDÉ DE DÉTECTION DE FUITE DE GAZ

(54) Title (JA): ガス漏洩検知システム及びガス漏洩検知方法

(57) Abstract:

(EN): This gas leak sensing system comprises: an enclosed chamber configured such that ventilation is possible, the enclosed chamber being provided with an air supply opening and an air discharge opening; a pipe through which flows a liquefied gas or an evaporation gas obtained by evaporating the liquefied gas, the pipe having a plurality of leak expectation locations scattered within the enclosed chamber; a first gas sensor disposed in the air discharge opening; and at least two second gas sensors having lower sensitivity to gas than does the first gas sensor, the at least two second gas sensors being disposed in the vicinity of at least two of the plurality of leak expectation locations, respectively.

(FR): L'invention concerne un système de détection de fuite de gaz comprenant : une chambre fermée configurée de telle sorte qu'une ventilation est possible, la chambre fermée étant pourvue d'une ouverture d'alimentation en air et d'une ouverture d'évacuation d'air ; un tuyau à travers lequel s'écoule un gaz liquéfié ou un gaz d'évaporation obtenu par évaporation du gaz liquéfié, le tuyau possédant une pluralité d'emplacements de fuite probable dispersés à l'intérieur de la chambre fermée ; un premier capteur de gaz disposé dans l'ouverture d'évacuation d'air ; et au moins deux deuxièmes capteurs de gaz ayant une sensibilité au gaz inférieure à celle du premier capteur de gaz, les au moins deux deuxièmes capteurs de gaz étant respectivement disposés au voisinage d'au moins deux de la pluralité d'emplacements de fuite probable.

(JA): ガス漏洩検知システムは、給気口及び排気口を備えて換気可能に構成された密閉室と、液化ガス又はそれが気化した蒸発ガスが流れ、密閉室内に点在する複数の漏洩想定箇所を有する配管と、排気口に設置された第１ガス検知器と、第１ガス検知器よりもガス検知感度が低い少なくとも２つの第２ガス検知器であって、複数の漏洩想定箇所の少なくとも２つの近傍にそれぞれ設置された少なくとも２つの第２ガス検知器と、を備える。

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